

ABSTRACT

An exemplary embodiment of the present invention provides an apparatus for processing a substrate, the apparatus comprising: a processing chamber having a processing space therein for processing a substrate; a support unit for supporting the substrate in the processing space; a plasma generation chamber provided outside the processing chamber and having a discharge space for generating plasma from process gas; an adapter connected to the processing chamber and the plasma generation chamber and having a guide space configured to guide the plasma generated in the discharge space to the processing chamber; and a baffle assembly disposed in the processing space, the guide space, or between the processing space and the guide space, wherein the baffle assembly includes: a baffle plate having a plurality of baffle holes providing passages for gas flowing between the guide space and the processing space; a fastening member configured to fasten the baffle plate to the processing chamber or the adapter; and a cover surrounding a fastening space in which the fastening member is positioned so that the fastening member is not exposed to the processing space.

FIG. 3